

a' cont. direction. A measuring mechanism 20 is provided to the Z-axis slider 16 movably in X-axis direction (measurement direction).

Page 12, lines 15-18, delete current paragraph and insert therefore:

a2 As shown in Fig. 2, the surface texture measuring machine 1 has the measuring machine body 1A and a measurement controller 50 for controlling the measuring machine body 1A for adjusting orientation of the workpiece 17.

Page 13, lines 30-33, delete current paragraph and insert therefore:

a3 In step 180, swivel inclination angle δ is calculated based on the coordinates values (X_s , Y_s) and (X_e , Y_e) obtained in steps 140 and 170 according to a formula of: $\tan \delta = (Y_e - Y_s) / (X_e - X_s)$, and swivel correction angle ds is further obtained.

Page 13, line 53- page 14, line 3, delete current paragraph and insert therefore:

a4 As shown in Fig. 3, when the distance between the rotation fulcrum A of the swivel and manipulation point B (a position where the swivel is pushed and pulled) of the swivel Digimatic micrometer head 42 is L and inclination angle of the swivel is δ , since $\tan \delta = (ds / L)$, the operation amount ds of the swivel Digimatic micrometer head can be represented as:

$$ds = L \tan \delta.$$

Page 18, lines 23-28, delete current paragraph and insert therefore:

a5 Specifically, as shown in Fig. 12, when the initial inclination angle of the stage 71, i.e. the inclination line C is parallel to the base line N and the angle of the center locus M relative to the base line N is θ_1 , accurate operation amount Δh can be obtained according to formula of $\Delta h = r \cdot \sin \theta_1$. Here, r represents a distance from the fulcrum A of the stage 71 to the point of action B.

Page 18, lines 29-35, delete current paragraph and insert therefore:

a6 On the other hand, when the inclination line C of the stage 71 is not parallel to the base line N but is rising in the right direction relative to the base line N, turn angle thereof

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cont. can be represented as θ_2 as shown in Fig. 12. When the stage is manipulated for Δh from a position remote from the base line N, the stage is manipulated at a steeper position for an angle away from the base line N as compared to manipulation for Δh from a horizontal position, so that θ_2 becomes smaller than θ_1 ($\theta_1 > \theta_2$).

Page 19, line 28- page 20, line 2, delete current paragraph and insert therefore:

a7 Fig. 13(A) shows a measurement of inclination of a measurement surface of the workpiece, where the initial inclination of the inclination line C declines rightward by an absolute quantity ht relative to the inclination adjustment reference position P. Since the inclination angle of the inclination line C relative to the base line N including the inclination adjustment reference position P is θ_t and the inclination angle of the measurement surface of the workpiece relative to the base line N including the inclination adjustment reference position P is θ_w , it is necessary to turn the stage 71 by θ_w relatively. However, as mentioned above, since the error can be caused, the relative minute displacement at the point of action B for turning only by θ_w relative to the base line N cannot be uniformly decided.

Page 20, lines 3-6, delete current paragraph and insert therefore:

a8 In this case, as shown in Fig. 13(B), the inclination of the measurement surface of the workpiece (center locus) can be coincided with the base line without error by setting the manipulated valuable hc equal to an absolute value from P where the turning angle is $\theta_c (= \theta_t + \theta_w)$.

IN THE CLAIMS:

[Please replace claim 3 as follows:]

a9 3. (Amended) The surface texture measuring machine according to Claim 2, wherein the Y-axis adjustment means, the swivel adjustment means and the inclination adjustment means respectively include a micrometer head.